

IH1611 2014

Material Properties and Formulas

Physical Constants

DESCRIPTION	SYMBOL	VALUE
Elementary charge	q	$1.60 \cdot 10^{-19} \text{ C}$
Electron volt	eV	$1.60 \cdot 10^{-19} \text{ J}$
Boltzmann's constant	k	$1.38 \cdot 10^{-23} \text{ J/K} = 8.62 \cdot 10^{-5} \text{ eV/K}$
Free electron mass	m_0	$9.11 \cdot 10^{-31} \text{ kg}$
Permittivity of free space	ϵ_0	$8.85 \cdot 10^{-12} \text{ F/m}$
Planck's constant	h	$6.63 \cdot 10^{-34} \text{ Js}$
Reduced Planck's constant ($\hbar/2\pi$)	$\hbar$	$1.05 \cdot 10^{-34} \text{ Js}$
Speed of light in vacuum	c	$3.00 \cdot 10^8 \text{ m/s}$
Thermal voltage at $T=300 \text{ K}$	kT/q	0.0259 V
Wavelength of 1 eV photon	λ	$1.24 \cdot \mu\text{m}$

Unit Conversion

QUANTITY	SYMBOL	VALUE/DIMENSION
Micrometer, micron	μm	$1 \mu\text{m} = 10^4 \text{ \AA} = 10^3 \text{ nm} = 10^{-4} \text{ cm}$
Nanometer	nm	$1 \text{ nm} = 10 \text{ \AA} = 10^{-3} \mu\text{m} = 10^{-7} \text{ cm}$
Ångström	$\text{\AA}$	$1 \text{ \AA} = 10^{-4} \mu\text{m} = 10^{-8} \text{ cm} = 10^{-10} \text{ m}$
Electric charge (Coulomb)	C	$\text{A} \cdot \text{s}$
Current (Ampere)	A	C/s
Frequency (Hertz)	Hz	$1/\text{s}$
Energy (Joule)	J	$\text{N} \cdot \text{m}$
Power (Watt)	W	J/s
Potential (Volt)	V	W/A
Conductance (Siemens)	S	A/V
Resistance (Ohm)	Ω	V/A
Capacitance (Farad)	F	C/V

PERIODIC TABLE

Atomic Properties of the Elements

NIST
National Institute of Standards and Technology
Technology Administration, U.S. Department of Commerce

Frequently used fundamental physical constants
For the most accurate values of these and other constants, visit physics.nist.gov/constants
1 second = 9 192 631 770 periods of radiation corresponding to the transition between the two hyperfine levels of the ground state of ^{133}Cs
speed of light in vacuum c 299 792 458 m s $^{-1}$ (exact)
Planck constant h 6.626 069 57 × 10 $^{-34}$ J s (exact)
elementary charge e 1.602 176 634 × 10 $^{-19}$ C (exact)
electron mass m_e 9.109 383 56 × 10 $^{-31}$ kg
 $m_e c^2$ 0.511 MeV
proton mass m_p 1.672 621 63 × 10 $^{-27}$ kg
fine-structure constant α 1/137.035 999 074
Rydberg constant R_∞ 1.097 373 157 × 10 7 m $^{-1}$
 $R_\infty c$ 3.289 841 96 × 10 15 Hz
 $R_\infty h c$ 13.605 698 06 eV
Boltzmann constant k 1.380 658 52 × 10 $^{-23}$ J K $^{-1}$

Frequently used fundamental physical constants													Physics Laboratory										Standard Reference				He	
For the most accurate values of these and other constants, visit physics.nist.gov/constants													Laboratory				Data Group											
1 second = 9 192 631 770 periods of radiation corresponding to the transition between the two hyperfine levels of the ground state of ¹³³ Cs													physics.nist.gov				www.nist.gov/srd											
speed of light in vacuum c 299 792 458 m s ⁻¹ (exact)													Solids				Liquids				Gases							
Planck constant h 6.626 070 15 × 10 ⁻³⁴ J s (h = h/2π)													Artificially Prepared															
elementary charge e 1.602 22 × 10 ⁻¹⁹ C																												
electron mass m _e 9.109 4 × 10 ⁻³¹ kg																												
proton mass m _p 1.672 6 × 10 ⁻²⁷ kg																												
fine-structure constant α 1/137.036																												
Rydberg constant R _∞ 10 973 732 m ⁻¹																												
Boltzmann constant k 1.380 7 × 10 ⁻²³ J K ⁻¹																												

Atomic Number
58

Ground-state Level
 1G_1

Symbol
Ce

Name
Cerium

Atomic Weight
140.116

Ground-state Configuration
[Xe]4f 1 5d 0 6s 2

Ionization Energy (eV)
5.5387

¹Based upon ^{12}C . () indicates the mass number of the most stable isotope.

For a description of the data, visit physics.nist.gov/data

NIST SP 966 (September 2003)

Mathematical Formulas

GAMMA FUNCTION

$$\int_0^{\infty} x^{n-1} e^{-x} dx = \Gamma(n)$$

$$\Gamma(1) = \Gamma(2) = 1 \quad \Gamma(3) = 2 \quad \Gamma(4) = 6$$

$$\Gamma\left(\frac{1}{2}\right) = \sqrt{\pi} \quad \Gamma\left(\frac{3}{2}\right) = \frac{\sqrt{\pi}}{2} \quad \Gamma\left(\frac{5}{2}\right) = \frac{3\sqrt{\pi}}{4}$$

HYPERBOLIC FUNCTIONS

$$\sinh x = \frac{e^x - e^{-x}}{2}$$

$$\cosh x = \frac{e^x + e^{-x}}{2}$$

$$\tanh x = \frac{e^x - e^{-x}}{e^x + e^{-x}}$$

$$\operatorname{sech} x = \frac{2}{e^x + e^{-x}}$$

$$\operatorname{csch} x = \frac{2}{e^x - e^{-x}}$$

$$\coth x = \frac{e^x + e^{-x}}{e^x - e^{-x}}$$

MACLAURIN SERIES EXPANSIONS

$$e^x = \sum_{n=0}^{\infty} \frac{x^n}{n!} = 1 + x + \frac{x^2}{2!} + \frac{x^3}{3!} + \cdots \text{ for all } x$$

$$\sinh x = \sum_{n=0}^{\infty} \frac{x^{2n+1}}{(2n+1)!} = x + \frac{x^3}{3!} + \frac{x^5}{5!} + \cdots \text{ for all } x$$

$$\cosh x = \sum_{n=0}^{\infty} \frac{x^{2n}}{(2n)!} = 1 + \frac{x^2}{2!} + \frac{x^4}{4!} + \cdots \text{ for all } x$$

$$\tanh x = \sum_{n=1}^{\infty} \frac{B_{2n} 4^n (4^n - 1)}{(2n)!} x^{2n-1} = x - \frac{1}{3}x^3 + \frac{2}{15}x^5 - \frac{17}{315}x^7 + \cdots \text{ for } |x| < \frac{\pi}{2}$$

LINEAR DIFFERENTIAL EQUATIONS

$$y = y_{hom} + y_{part} \quad y_{part} \text{ can be found by assuming a polynomial of the same degree as } P(x)$$

$$\text{FIRST ORDER:} \quad \frac{dy}{dx} + ay = P(x) \quad y_{hom} = Ae^{-ax}$$

$$\text{SECOND ORDER:} \quad \frac{d^2y}{dx^2} - a^2y = P(x) \quad y_{hom} = Ae^{-ax} + Be^{ax}$$

Semiconductor Formulas

Fermi-Dirac statistics	$f(E) = \frac{1}{1 + e^{\frac{(E-E_F)}{kT}}}$	k: Boltzmann's constant [eV/K] T: Temperature [K] E _F : Fermi Level [eV]
Poisson's equation	$\frac{d^2V}{dx^2} = -\frac{dE}{dx} = -\frac{\rho}{\epsilon_s}$	V: Potential [V] E: Electric field [V/cm] ρ: Charge density [C/cm ³] ε _s : Semiconductor permittivity [F/cm]
Continuity equation for electrons	$\frac{\partial n}{\partial t} = \frac{1}{q} \frac{\partial J_n}{\partial x} - \frac{n - n_o}{\tau_n} + G$	n: Electron carrier concentration [cm ⁻³] J _n : Electron current density [A/cm ²] τ _n : Electron recombination lifetime [s] G: External electron generation rate [cm ⁻³ s ⁻¹]
Continuity equation for holes	$\frac{\partial p}{\partial t} = -\frac{1}{q} \frac{\partial J_p}{\partial x} - \frac{p - p_o}{\tau_p} + G$	p: Hole carrier concentration [cm ⁻³] J _p : Hole current density [A/cm ²] τ _p : Hole recombination lifetime [s] G: External hole generation rate [cm ⁻³ s ⁻¹]
Einstein relationship	$D = \frac{kT}{q} \mu$	D: Diffusion coefficient of carriers [cm ² /s] μ: Mobility of carriers [cm ² /Vs]
Diffusion Length	$L = \sqrt{D\tau}$	D: Diffusion coefficient of carriers [cm ² /s] τ: Carrier recombination lifetime [s]
MOS capacitor equations	$V_g = V_{fb} + \phi_s + V_{ox}$ $V_{ox} = -\frac{Q_{sub}}{C_{ox}}$	V _g : Gate voltage [V] V _{fb} : Flatband voltage [V] φ _s : Surface potential [V] V _{ox} : Voltage over oxide [V] Q _{sub} : Charge in semiconductor [C/cm ²] C _{ox} : Oxide capacitance [F/cm ²]
NMOSFET	$V_t = V_{t0} + (m - 1)V_{sb}$ $m = 1 + \frac{\epsilon_s T_{oxe}}{\epsilon_{ox} W_{dmax}}$ $I_{ds} = \frac{W}{L} C_{oxe} \mu_{ns} (V_{gs} - V_t - \frac{m}{2} V_{ds}) V_{ds}$	V _t : threshold voltage [V] V _{t0} : threshold voltage at zero V _{sb} [V] m: bulk-charge factor [] V _{sb} : Potential between source and bulk [V] ε _s : Permittivity of semiconductor [F/cm] T _{oxe} : Effective oxide thickness [cm] ε _{ox} : Permittivity of oxide [F/cm] W _{dmax} : Maximum depletion layer width [cm] W: Gate width [cm] L: Gate length [cm] C _{oxe} : Effective oxide capacitance [F/cm ²] μ _{ns} : Electron surface mobility [cm ² /Vs] V _{gs} : Potential between gate and source [V] V _{ds} : Potential between drain and source [V]

Work function and Schottky barrier heights of metals and silicides to Si

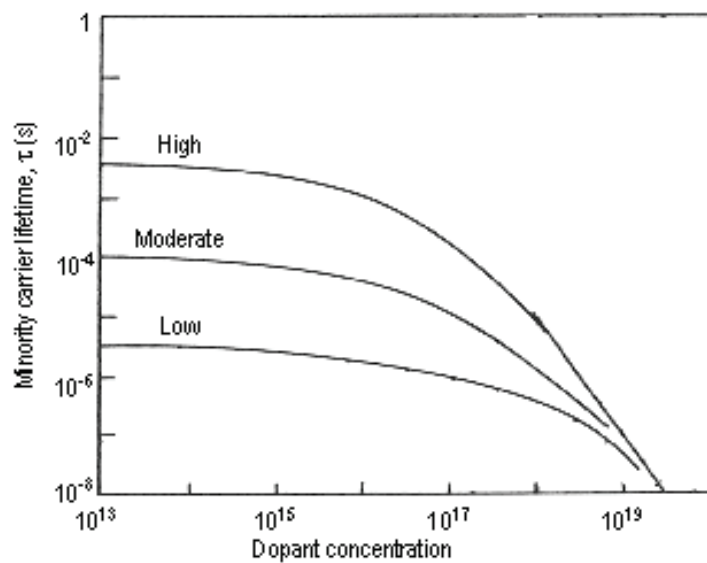
Metal	Mg	Ti	Cr	W	Mo	Pd	Au	Pt
ϕ_{Bn} (V)	0.4	0.5	0.61	0.67	0.68	0.77	0.8	0.9
ϕ_{Bp} (V)		0.61	0.50		0.42		0.3	
Work Function ψ_M (V)	3.7	4.3	4.5	4.6	4.6	5.1	5.1	5.7

Silicide	ErSi _{1.7}	HfSi	MoSi ₂	ZrSi ₂	TiSi ₂	CoSi ₂	WSi ₂	NiSi ₂	Pd ₂ Si	PtSi
ϕ_{Bn} (V)	0.28	0.45	0.55	0.55	0.61	0.65	0.67	0.67	0.75	0.87
ϕ_{Bp} (V)			0.55	0.55	0.49	0.45	0.43	0.43	0.35	0.23

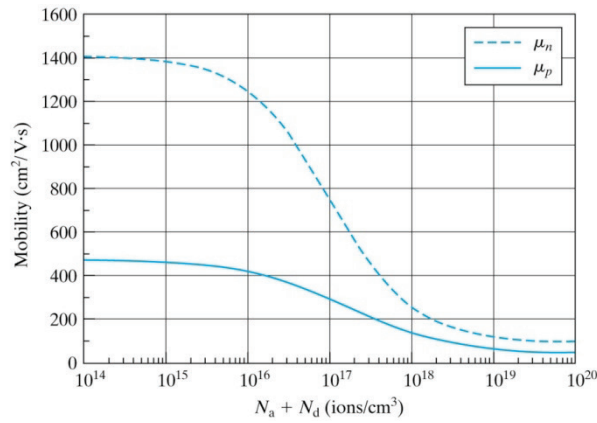
Egenskaper hos Si (T=300 K)

QUANTITY	SYMBOL	VALUE/DIMENSION
Bandgap	E_g	1.12 eV, indirect
Intrinsic carrier concentration	n_i	10^{10} cm^{-3}
Effectiv Density of states in E_c	N_c	$2.8 \cdot 10^{19} \text{ cm}^{-3}$
Effectiv Density of states in E_v	N_v	$1.0 \cdot 10^{19} \text{ cm}^{-3}$
Electron effective mass	m_n/m_0	0.26
Hole effective mass	m_p/m_0	0.39
Electron/Hole thermal velocity	v_{th}^e/v_{th}^h	$2.3 \cdot 10^7 / 1.7 \cdot 10^7 \text{ cm/s}$
Electron affinity	χ	4.05 eV
Relative permittivity	ϵ_r	11.9
Electric breakdown field	ϵ_{crit}	$\sim 4 \cdot 10^5 \text{ V/cm}$

Si carrier lifetime τ in low, moderate and high quality Si crystals



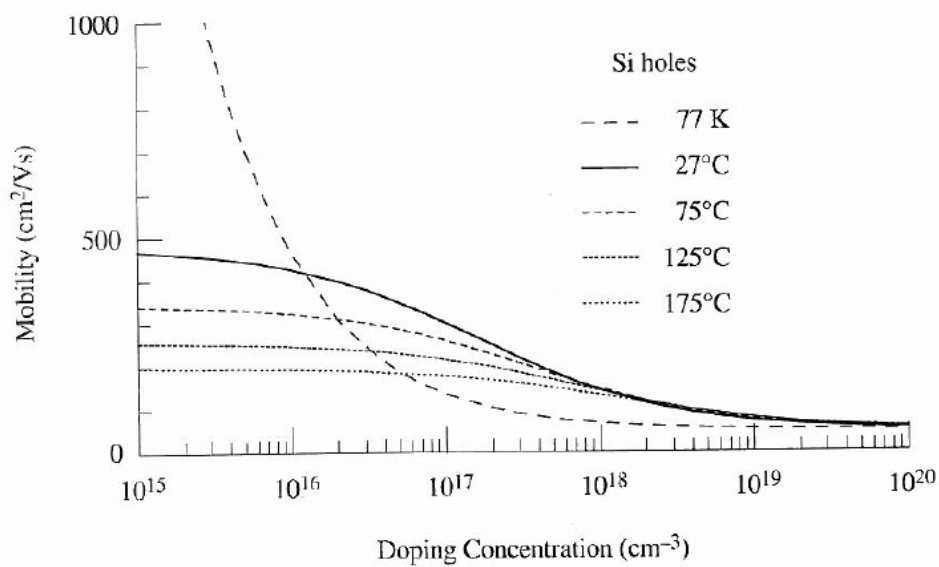
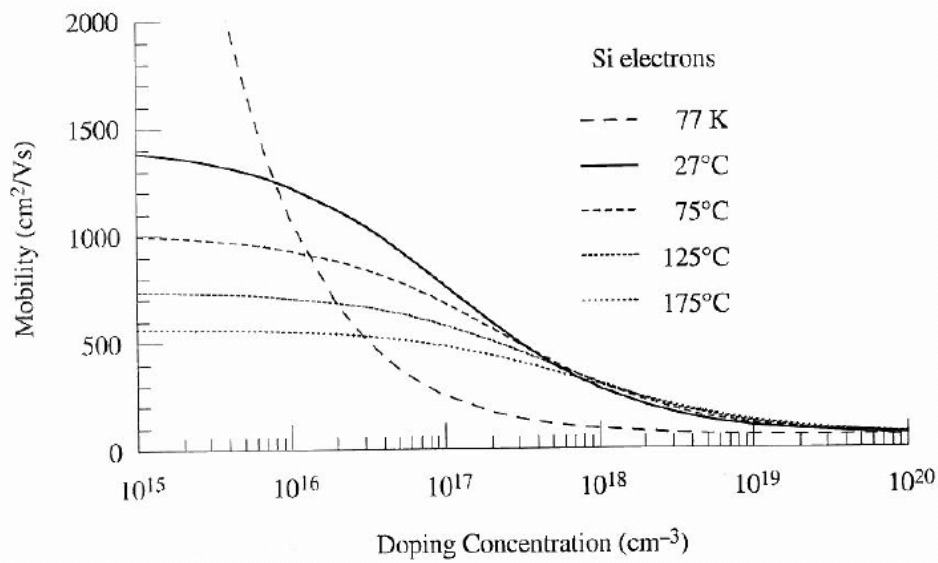
Si electron and hole mobility at $T=300\text{ K}$ [cm^2/Vs]



$$\mu_n = \frac{1318}{1 + \left(\frac{N_a + N_d}{10^{17}} \right)^{0.85}} + 92$$

$$\mu_p = \frac{420}{1 + \left(\frac{N_a + N_d}{1.6 \cdot 10^{17}} \right)^{0.7}} + 50$$

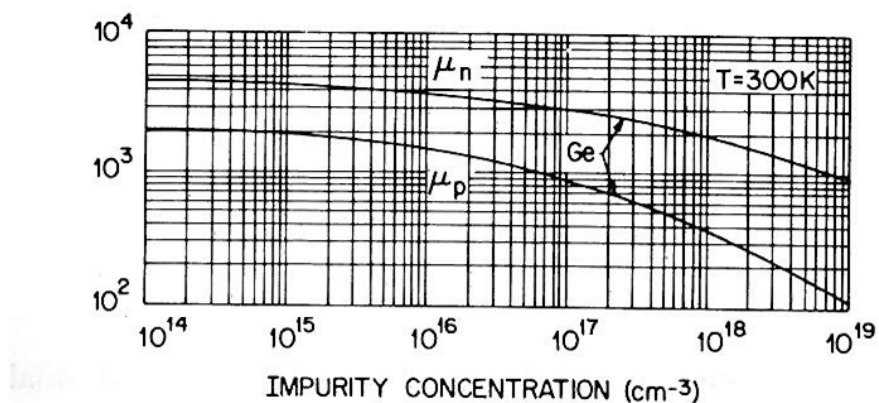
Si electron and hole mobility a various temperatures



Egenskaper hos Ge (T=300 K)

QUANTITY	SYMBOL	VALUE/DIMENSION
Bandgap	E_g	0.67 eV, indirect
Intrinsic carrier concentration	n_i	$2.4 \cdot 10^{13} \text{ cm}^{-3}$
Effectiv Density of states in E_c	N_c	$1.0 \cdot 10^{19} \text{ cm}^{-3}$
Effectiv Density of states in E_v	N_v	$6.0 \cdot 10^{18} \text{ cm}^{-3}$
Electron effective mass	m_n/m_0	0.12
Hole effective mass	m_p/m_0	0.21
Electron/Hole thermal velocity	v_{th}^e/v_{th}^h	$3.1 \cdot 10^7 / 1.9 \cdot 10^7 \text{ cm/s}$
Electron affinity	χ	4.0 eV
Relative permittivity	ϵ_r	16
Electric breakdown field	ϵ_{crit}	$\sim 2 \cdot 10^5 \text{ V/cm}$

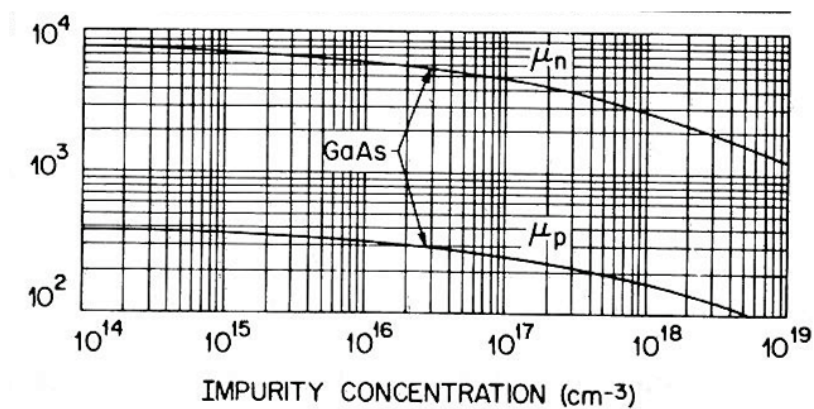
Ge electron and hole mobility at T=300 K [cm^2/Vs]



Egenskaper hos GaAs (T=300 K)

QUANTITY	SYMBOL	VALUE/DIMENSION
Bandgap	E_g	1.42 eV, direct
Intrinsic carrier concentration	n_i	$9 \cdot 10^6 \text{ cm}^{-3}$
Effectiv Density of states in E_C	N_c	$4.7 \cdot 10^{17} \text{ cm}^{-3}$
Effectiv Density of states in E_v	N_v	$7.0 \cdot 10^{18} \text{ cm}^{-3}$
Electron effective mass	m_n/m_0	0.067
Hole effective mass	m_p/m_0	0.34
Electron/Hole thermal velocity	v_{th}^e/v_{th}^h	$4.4 \cdot 10^7 / 1.8 \cdot 10^7 \text{ cm/s}$
Electron affinity	χ	4.07 eV
Relative permittivity	ϵ_r	13.1
Electric breakdown field	ϵ_{crit}	$\sim 8 \cdot 10^5 \text{ V/cm}$

GaAs electron and hole mobility at T=300 K [cm^2/Vs]



Egenskaper hos GaP (T=300 K)

QUANTITY	SYMBOL	VALUE/DIMENSION
Bandgap	E_g	2.24 eV, indirect
Intrinsic carrier concentration	n_i	$\sim 1 \text{ cm}^{-3}$
Effectiv Density of states in E_c	N_c	$1.8 \cdot 10^{19} \text{ cm}^{-3}$
Effectiv Density of states in E_v	N_v	$1.9 \cdot 10^{19} \text{ cm}^{-3}$
Electron effective mass	m_n/m_0	0.30
Hole effective mass	m_p/m_0	0.71
Electron/Hole thermal velocity	v_{th}^e/v_{th}^h	$2 \cdot 10^7 / 1.3 \cdot 10^7 \text{ cm/s}$
Electron affinity	χ	3.8 eV
Relative permittivity	ϵ_r	11.1
Electric breakdown field	$\mathcal{E}_{crit}$	$\sim 10^6 \text{ V/cm}$

Egenskaper hos SiC (4H) (T=300 K)

QUANTITY	SYMBOL	VALUE/DIMENSION
Bandgap	E_g	3.2 eV, indirect
Intrinsic carrier concentration	n_i	-
Effectiv Density of states in E_c	N_c	$1.7 \cdot 10^{19} \text{ cm}^{-3}$
Effectiv Density of states in E_v	N_v	$2.5 \cdot 10^{19} \text{ cm}^{-3}$
Electron effective mass	m_n/m_0	0.39
Hole effective mass	m_p/m_0	0.82
Electron/Hole thermal velocity	v_{th}^e/v_{th}^h	$1.9 \cdot 10^7 / 1.2 \cdot 10^7 \text{ cm/s}$
Electron affinity	χ	3.91
Relative permittivity	ϵ_r	10
Electric breakdown field	$\mathcal{E}_{crit}$	$2.2 \cdot 10^6 \text{ V/cm}$